

Fig. S1. AFM topographic surface images for (A) a pristine quartz substrate, (B) a 15-cycle **ML** of **Pc1** on quartz and (C) a 8-cycle **ML** of **Pc2** on quartz . The observed scan area is $0.25 \mu\text{m} \times 0.25 \mu\text{m}$.

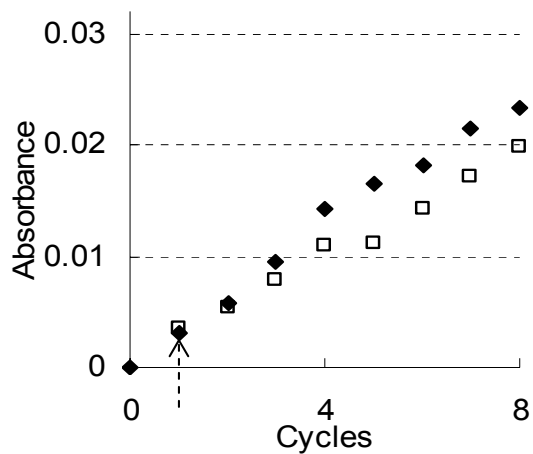


Fig. S2. Changes of absorbance at 670 nm of **Pc2** following the number of alternate dipping cycles for two different **TiO_x-Pc₂** MLs grown on a one-cycle **TiO_x-Pc₂** layer (◆) and on a SAM of **Pc₂** (□) (shown by the broken arrow) initially fabricated on a quartz substrate.

Table S1 XPS elemental analysis data for TiOx-**Pc** MLs^a

	C _{1s}	N _{1s}	O _{1s}	Si _{2p}	Ti _{2p}	Ti/ Pc ^b
14-cycle TiOx- Pc1	0.49	0.043	0.34	0.11	0.023	4.3
6-cycle TiOx- Pc2	0.54	0.058	0.31	0.071	0.028	3.8
6-cycle TiOx- Pc3	0.53	0.045	0.32	0.088	0.021	3.8

^a Measured at a take-off angle of 90° for the layers fabricated on quartz substrates. ^b (Ti_{2p} × 8)/N_{1s}.